

Defect Modeling of CNT Interconnects for System-in-Package Application

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Outline

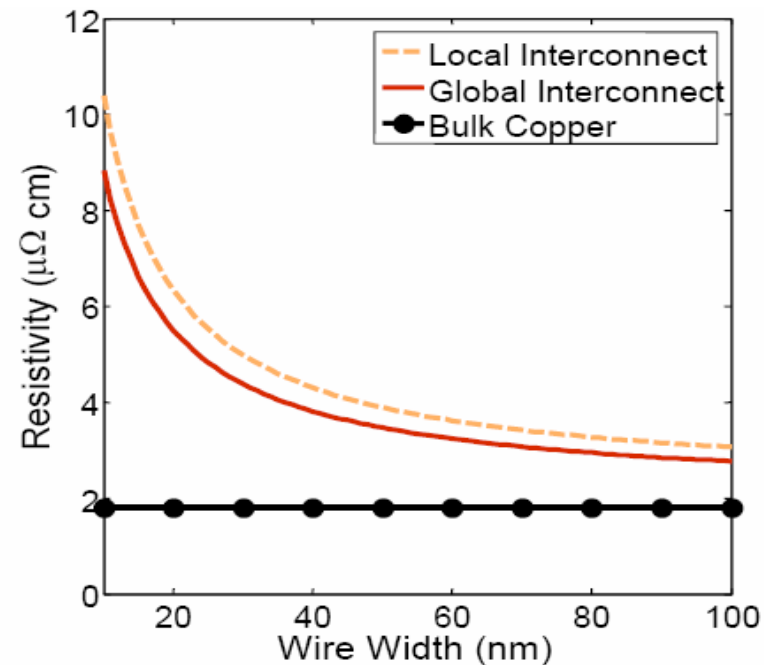
- Properties of carbon nanotubes (CNT)
- Predicting the performance of CNT interconnect
 - Circuit model of CNT interconnect.
 - Fault Model of CNT interconnect.
 - Fabrication of Bundle CNT-interconnect.
- Conclusion.

Interconnect and Technology scaling

- On chip communication is a bottleneck.
 - Copper interconnect currently plagued by delay, noise, and reliability problems
 - Electromigration also decreases reliability.
- Problem aggravated by interconnect scaling
 - Smaller wire dimensions
 - Process variations becoming an important reliability concern

Resistivity changes in copper wire with Technology

- Resistivity of copper interconnect increases as cross-sectional dimensions decreases(Dimensions on the order of mean free path of electrons).
- Radical alternative technology is required
- ITRS 2006.



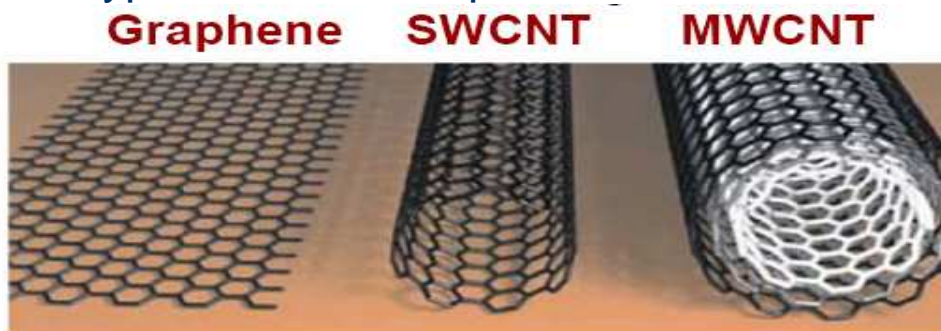
Carbon Nanotubes for On-chip Interconnects.

- Carbon nanotubes have been proposed as a possible replacement for on-chip interconnect.
 1. Large current density.
 2. Relatively low resistivity.
 3. Small dimensionality



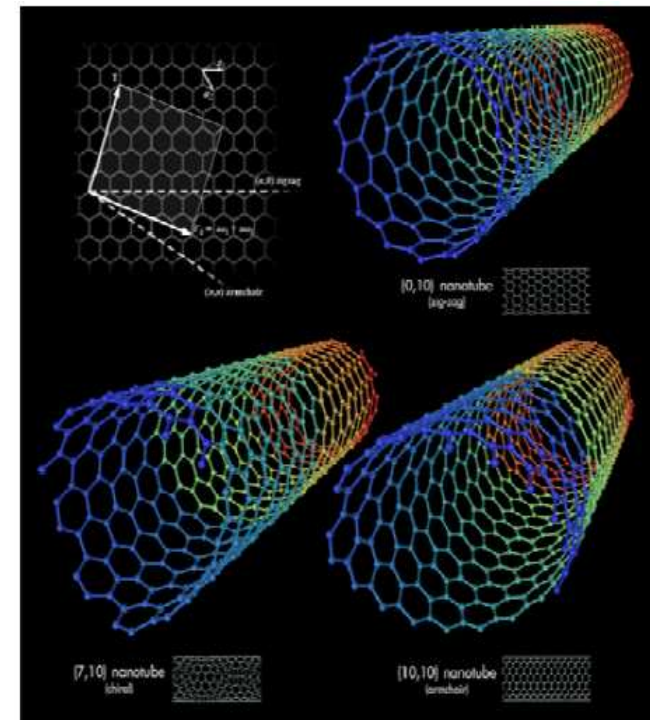
Types of Carbon Nanotube

- Single-walled carbon nanotubes (SWCNTs).
 1. Rolled single sheet of graphene.
 2. Typical diameter: 0.4 nm to 4.0 nm.
- Multi-walled carbon nanotubes (MWCNTs).
 1. Nested SWCNTs.
 2. Distance between layers: 0.34 nm.
 3. Typical diameter: up to 100 nm.



Single Walled CNT: Electrical Properties.

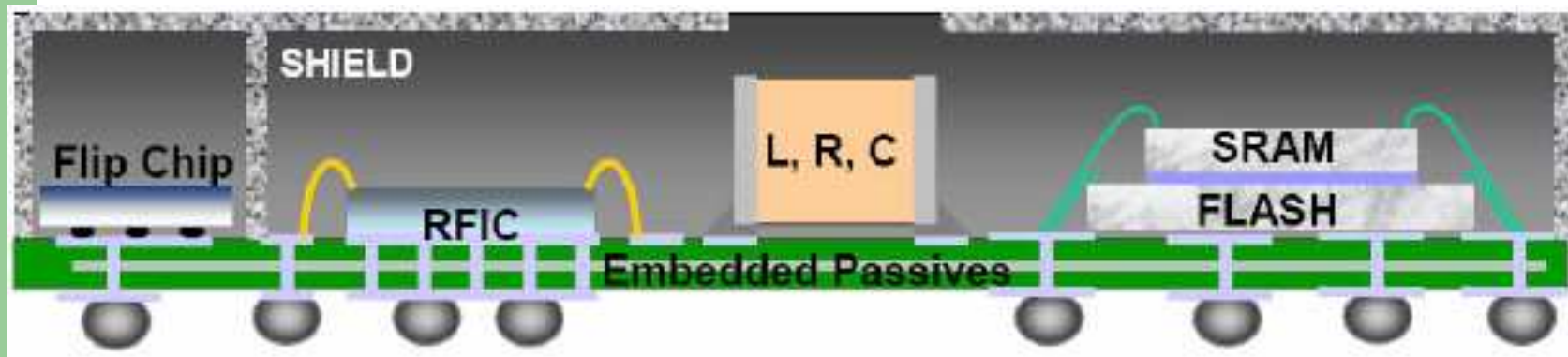
- SWCNTs exhibit either metallic or semiconducting behavior.
 - Chirality dependent.
 - 1/3 of possible SWCNT is Metallic.
- Strong carbon-carbon bonds allow large current densities $\sim 10^9 \text{ A/cm}^2$.



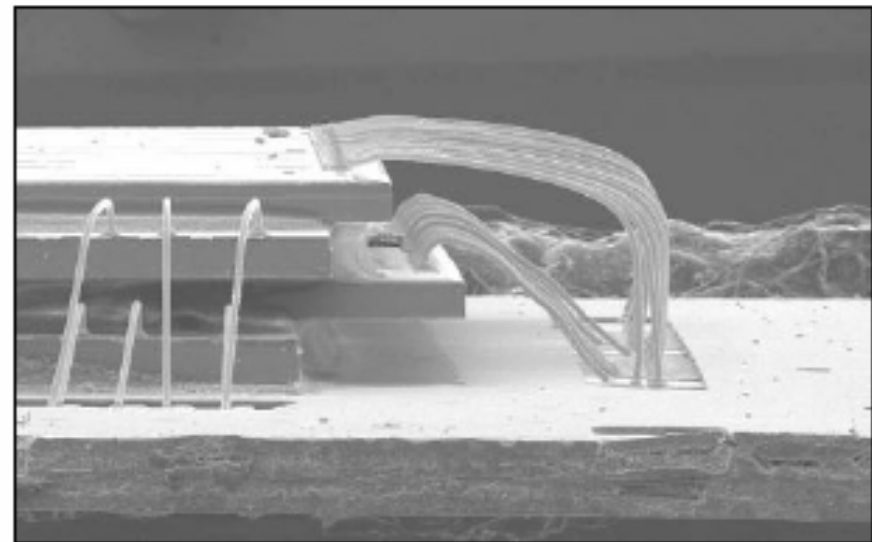
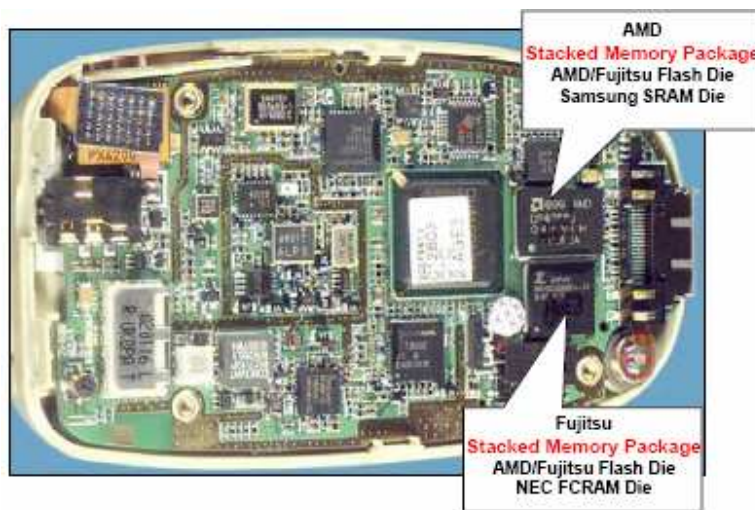
Carbon nanotube Bundles

- Bundles of Carbon nanotubes have been proposed for interconnect applications.
- Why Bundles?
 - High Current carrying capabilities
 - Reduced resistance (Single SWCNT has effective resistance of $\sim 6.5K$).
- Bundles of SWCNT have reduced resistance and effective inductance.

System in Package

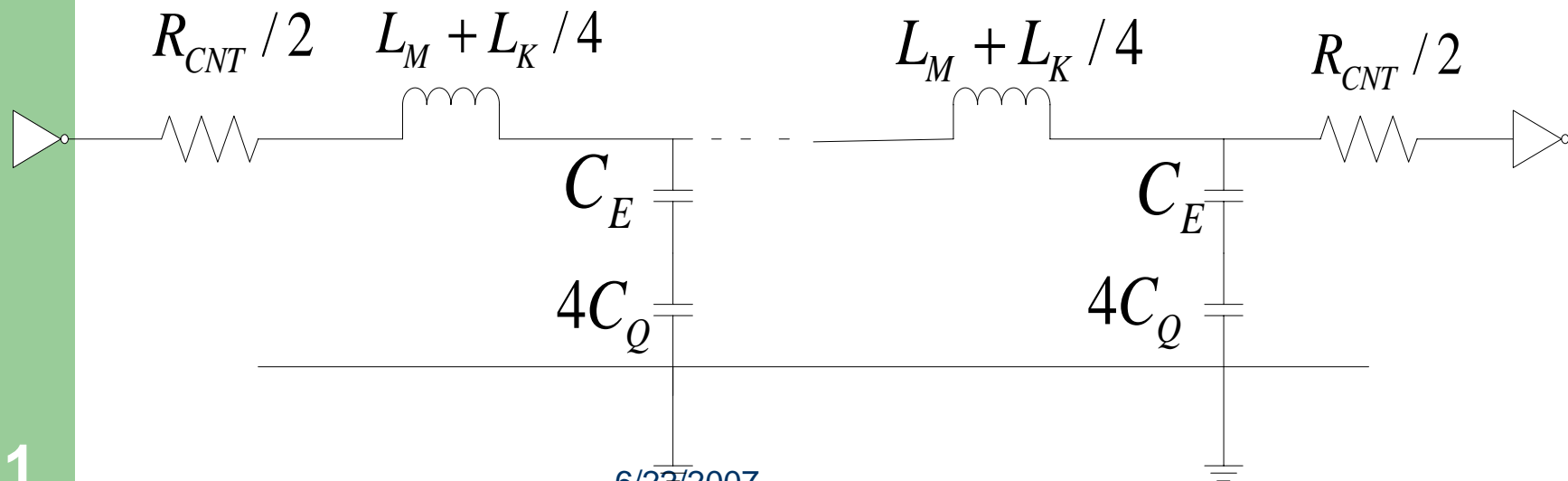


SiP Integration Levels



Circuit model of SWCNT

- Equivalent circuit model for SWCNT bundles
 1. Based on model for a single SWCNT from Burke [4].
 2. Captures experimentally verified resistance as well as theoretically predicted capacitive and inductive effects.



Electrostatic Capacitance

- To date, there is no accurate model to describe the electrostatic capacitive and inductive coupling between different CNT-bundles.
- The electrostatic capacitive and inductive couplings between CNT-bundles are strongly dependent on geometry, placement and distance of separation between individual CNT-bundle. They are also affected by permittivity and permeability of materials in different layers of SiP substrate in which these bundles are placed.
- Three Different models for determining Electrostatic capacitance between CNT-bundles.

PROPOSED CNT BUNDLE MODEL

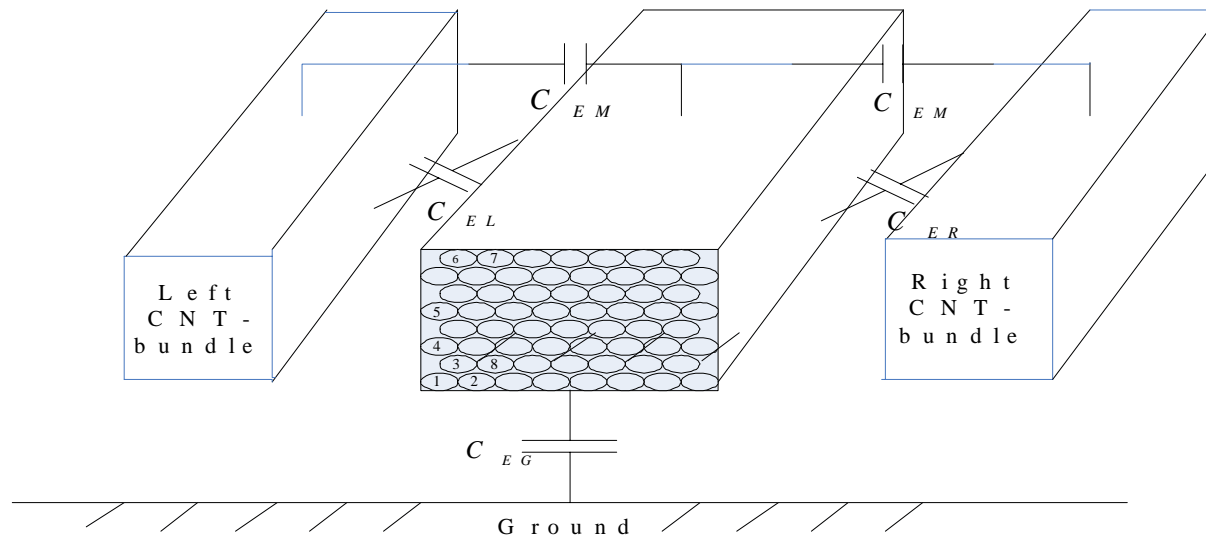
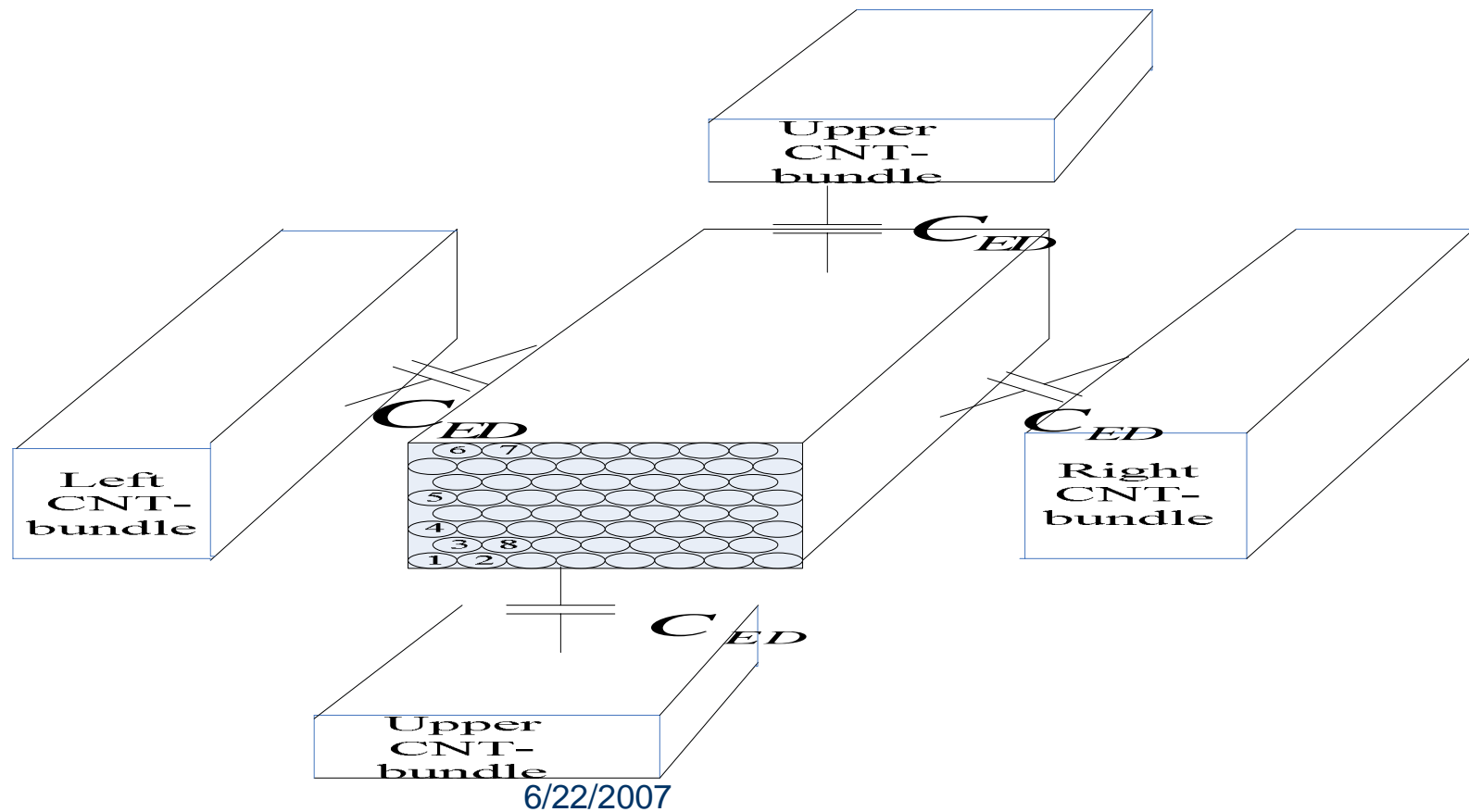
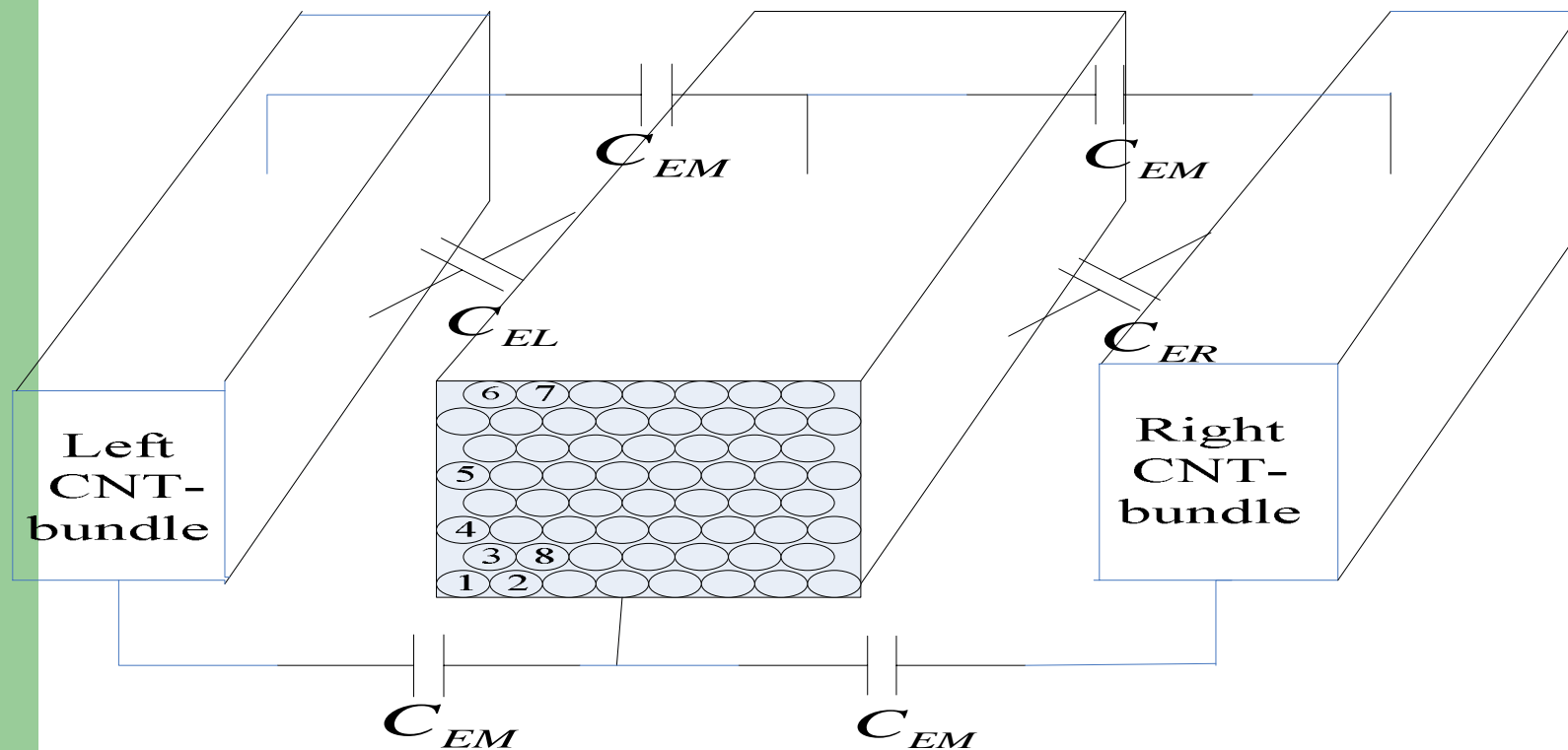


Fig. 1: Three CNT bundles in parallel with ground plane (geometry I).

Stacked CNT Bundle Model



Power Plane CNT-Bundle Model

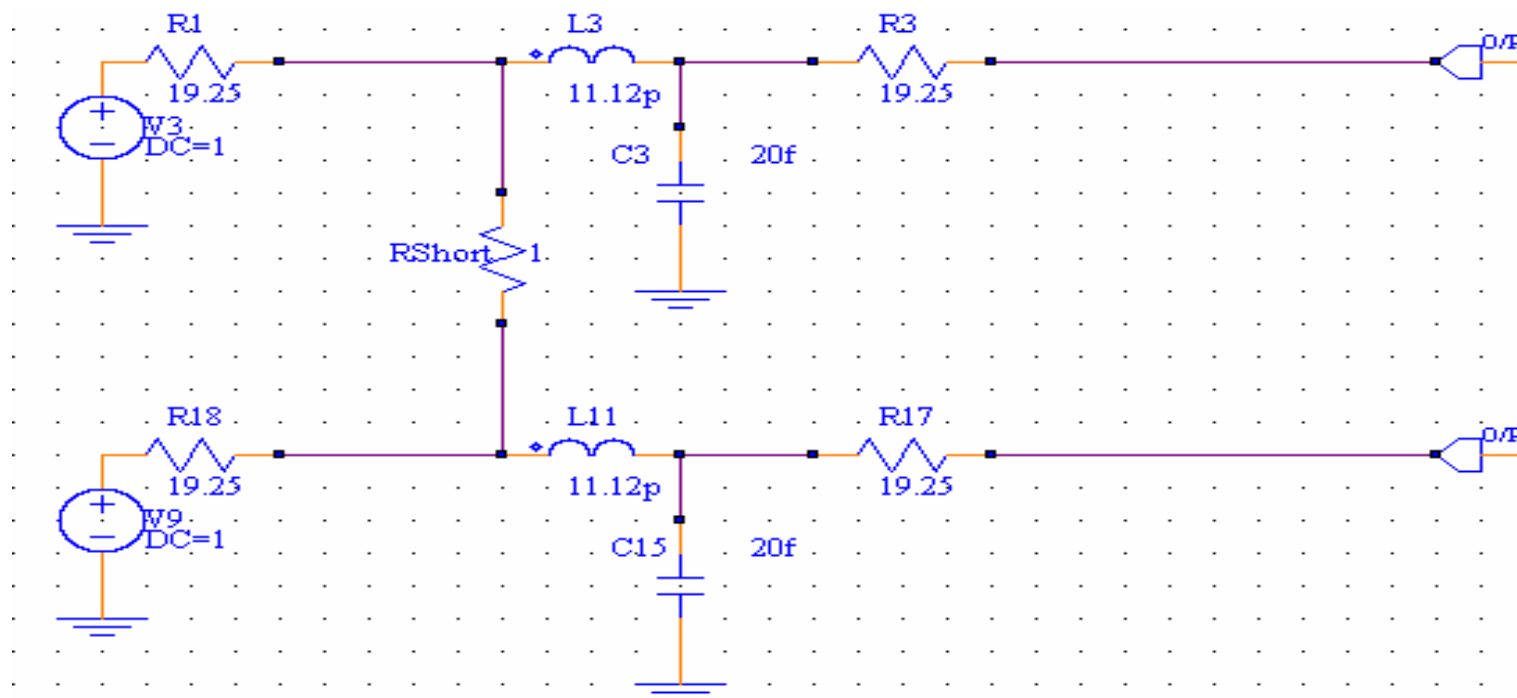


Defects in CNT-bundle Interconnect

- CNT-bundle interconnects in nano scale SiP design is affected by various parametric variations, manufacturing defects and process variations .
- Types of Defects
 - Short Defects.
 - Open Defects.

Shorts Defect Model

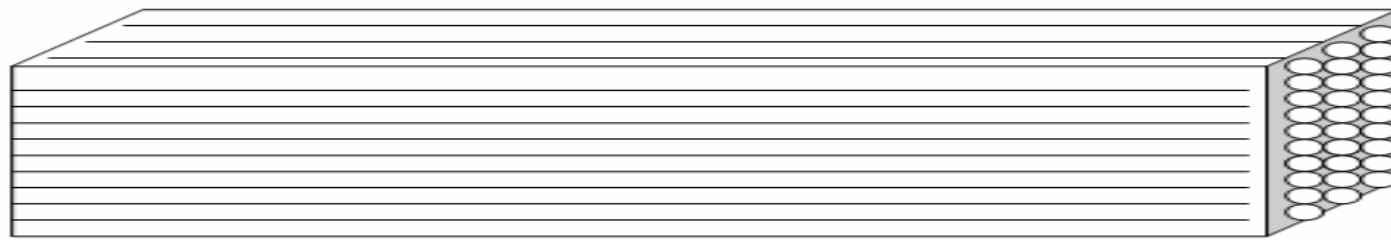
- A short defect is a connection between the two CNT-bundles that are merged and it forms a single bundle at a defective point.



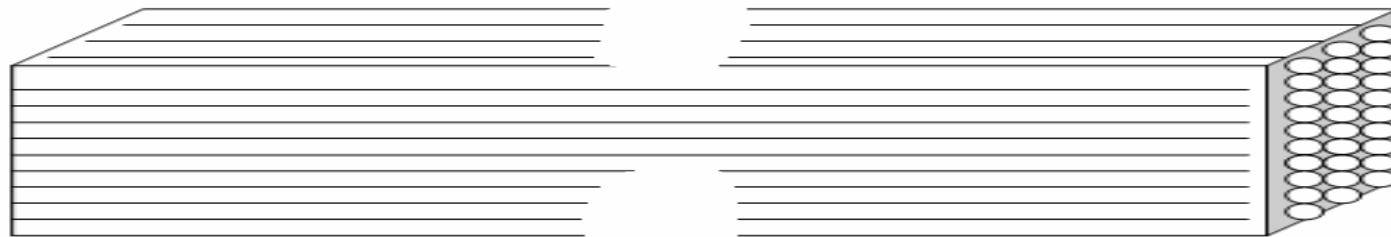
OPEN DEFECTS

- An open defect is a break in the connection in the CNT-bundle. Two major types of open defects that are important from nano interconnects point of view are
 - Complete Open
 - Partial Open

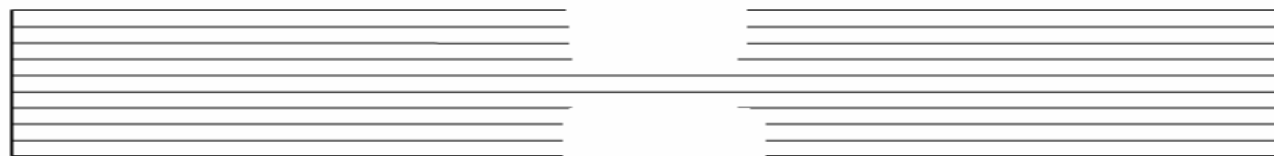
Physical Open Defects



(a)

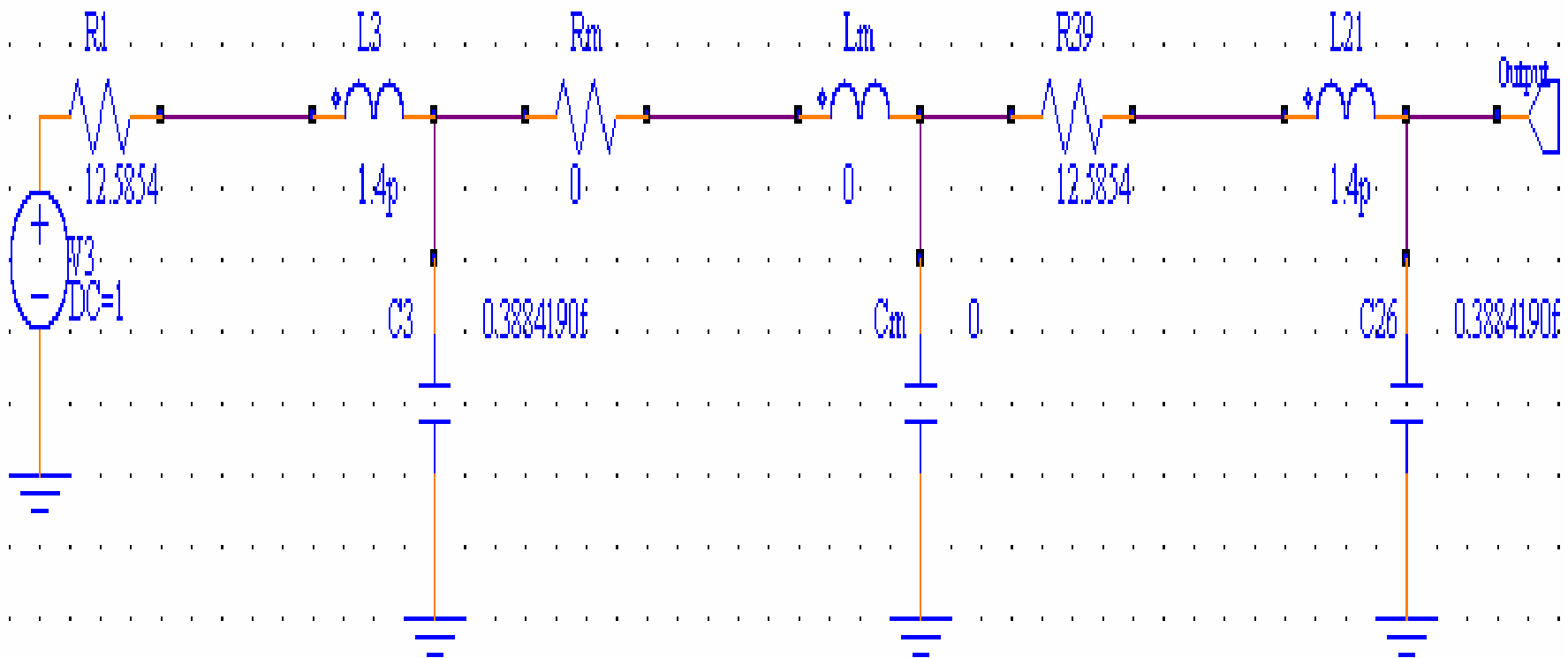


(b)

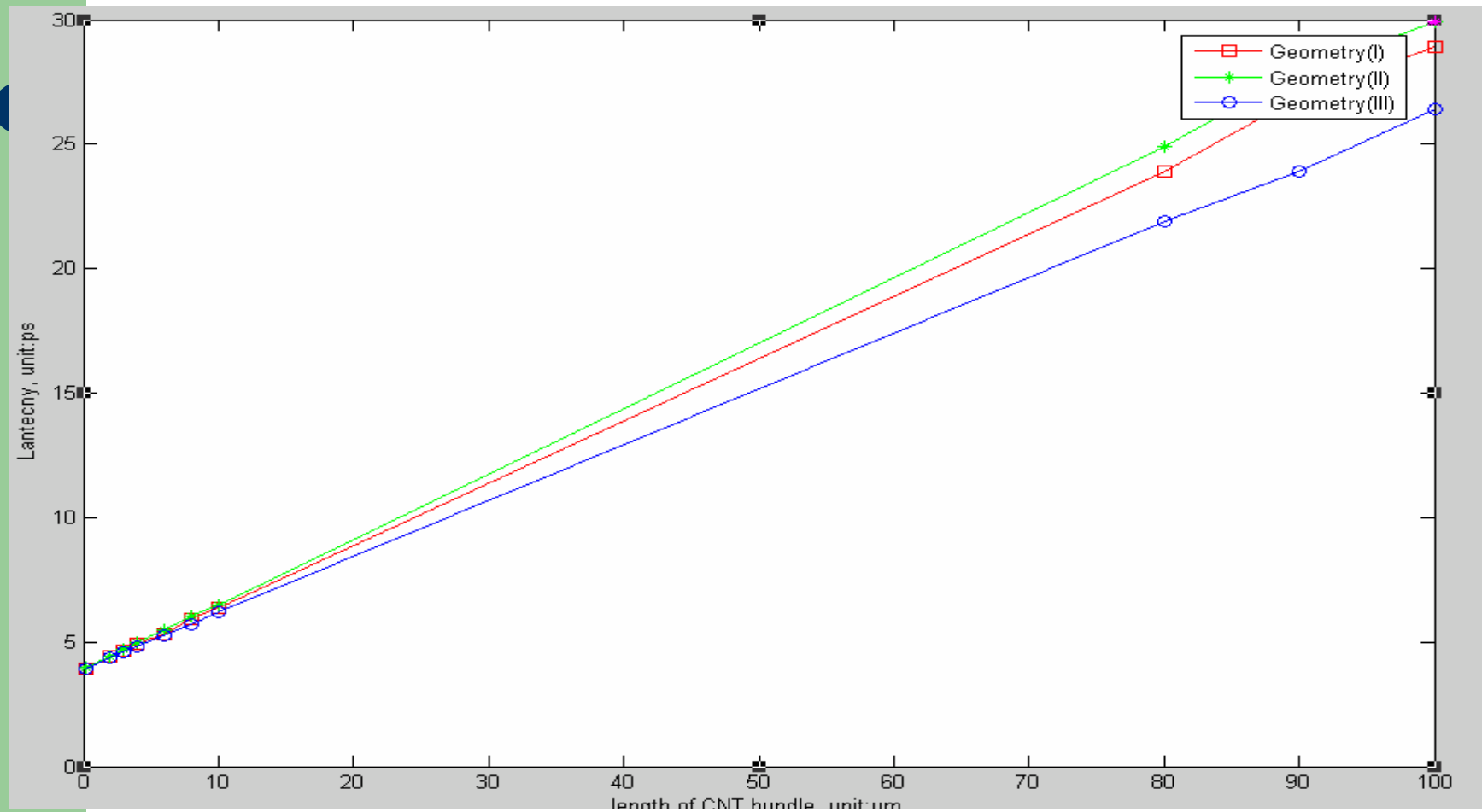


(c)

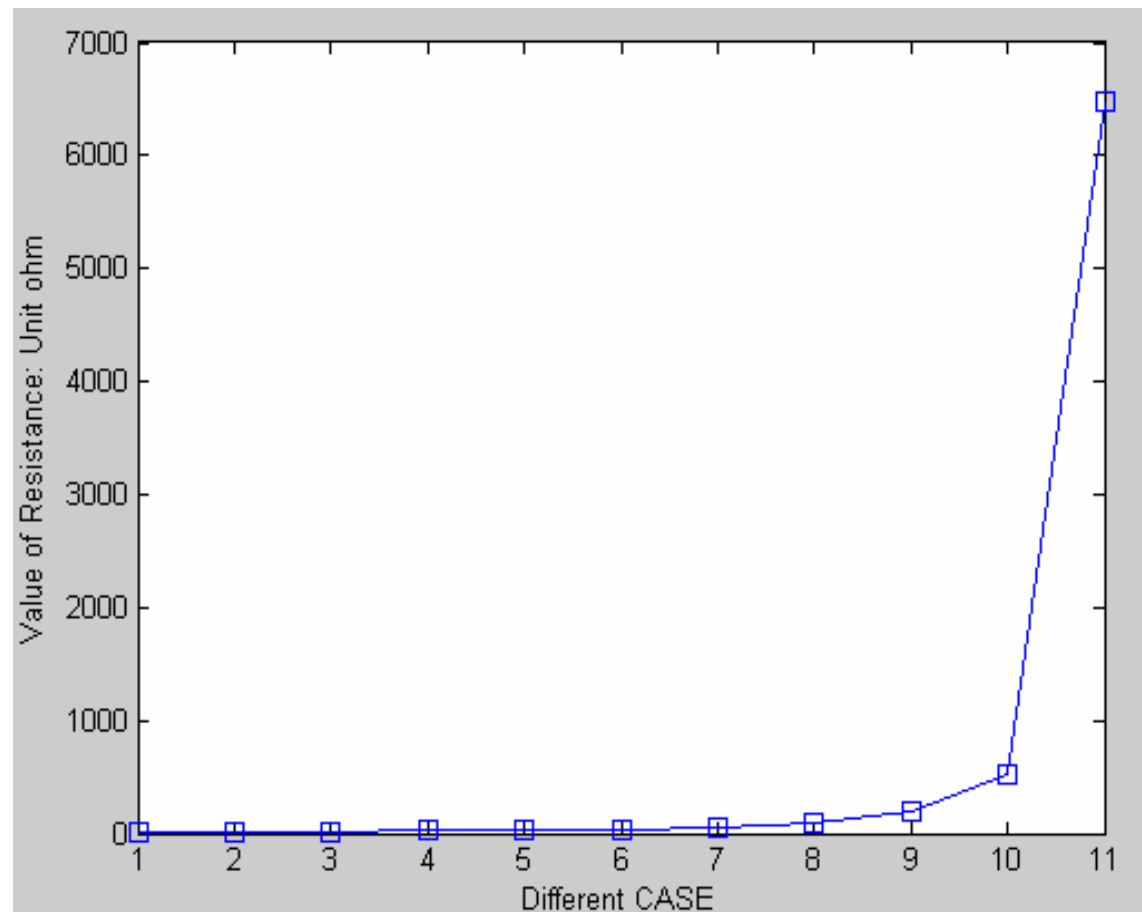
OPEN DEFECT MODEL



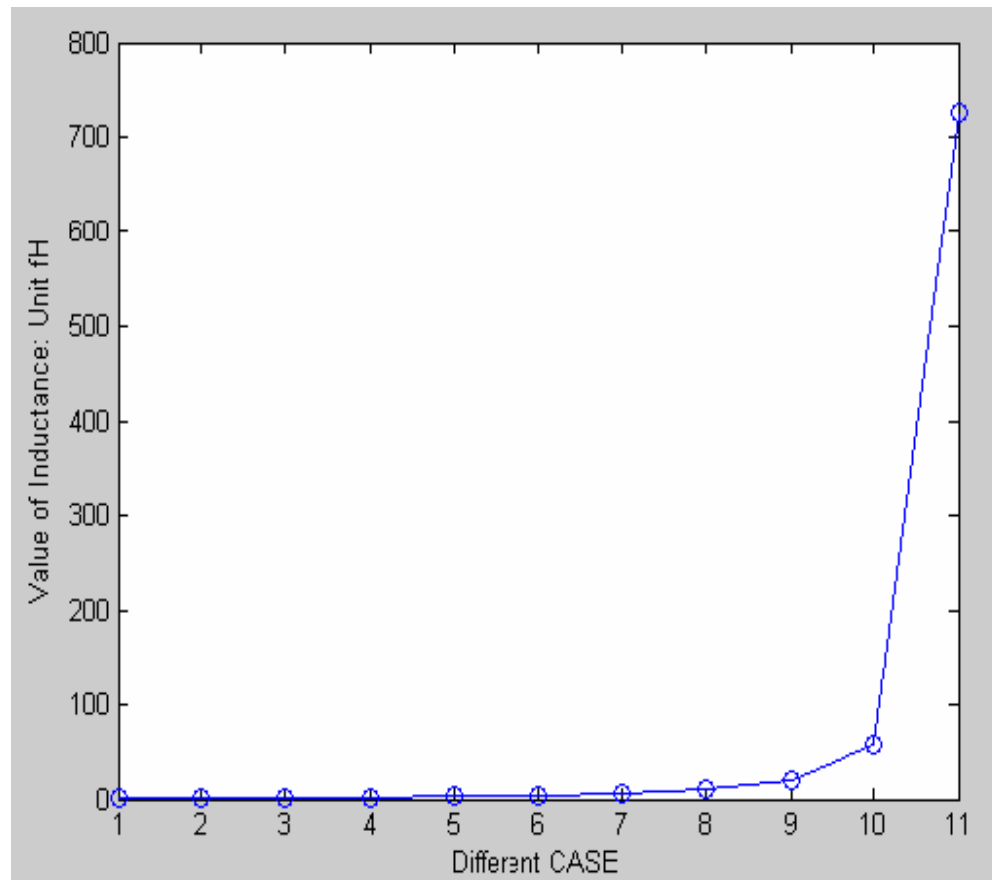
Latency variation in CNT-bundles



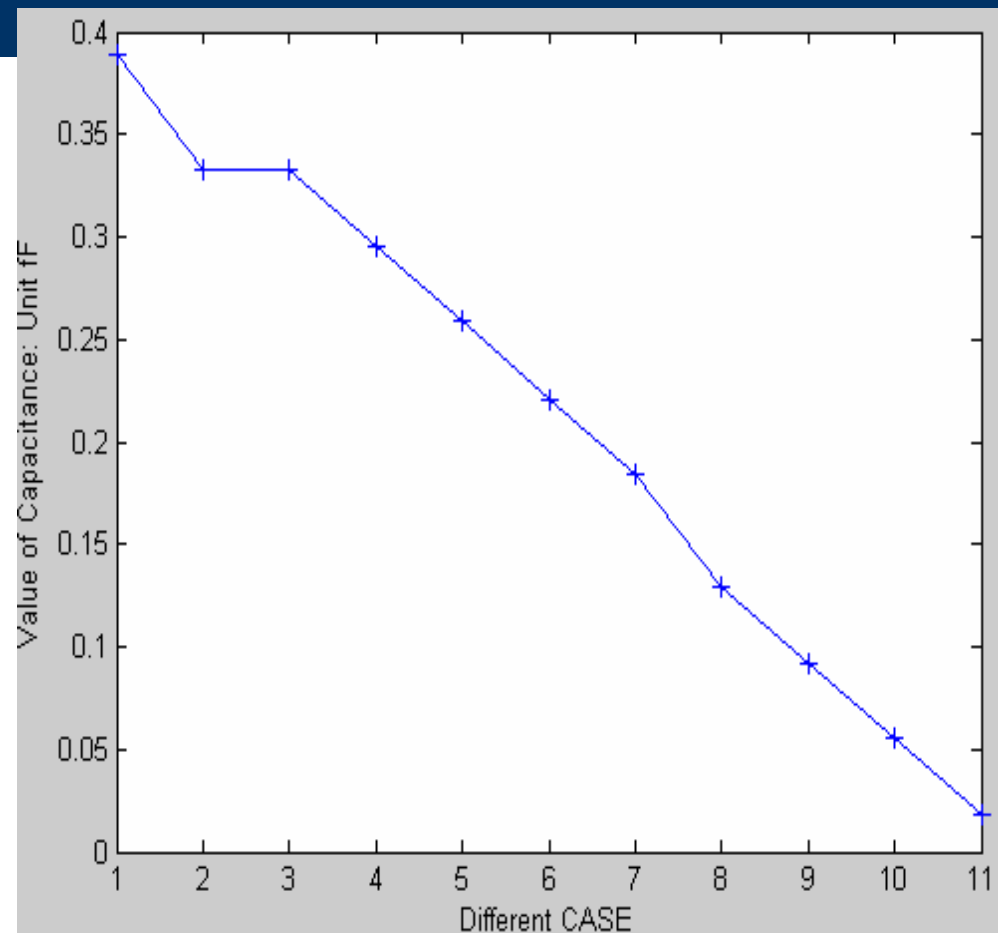
variation of effective resistance



Effective inductance



Effective Capacitance



CONCLUSIONS

- We proposed three different CNT-bundle architectures for nano scale interconnect applications in system-in-package.
- We compared the latency of the three architectures.
- We provided defect models of the CNT interconnects for open and shorts defects.
- Increase in resistance and inductance as the defect sizes increases whereas the effective capacitance decreases.

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Acknowledgement

- National Science Foundation